

METHOD FOR PURIFYING SEMICONDUCTOR GASES

ABSTRACT

This invention is directed a method for purifying an impure gas to produce an ultra-high purity gas comprising the steps of a) passing the impure liquefied gas through a first absorption means to remove impurities from the liquid phase therein to produce a first purified fluid; b) passing the first purified fluid through an evaporation means to remove impurities therein to produce a second purified gas; and c) passing the second purified gas through a second absorption means to remove impurities from the vapor phase therein to produce the ultra-high purity gas.